

DOCKET NO.: 206342US2



IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

TOSHIFUMI NAGAIWA, ET AL.

SERIAL NO: 09/840,178

FILED: APRIL 24, 2001

FOR: WORKTABLE DEVICE AND
PLASMA PROCESSING
APPARATUS FOR
SEMICONDUCTOR PROCESS

: EXAMINER: 1763

: GROUP ART UNIT: KACKAR, R.

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

This is an amendment responsive to the Office Action dated June 20, 2002, please
amend the above-identified application as follows:

IN THE CLAIMS

Please cancel Claims 4, 8, 10, 11, 13 and 18 without prejudice.

1. (Amended) A worktable device for a semiconductor process, comprising:

a worktable having a main surface for supporting a target substrate and a sub-surface
disposed around said main surface;

A
a cooling mechanism disposed in said worktable and configured to supply cold to the
main surface and the sub-surface;

D
a focus ring placed on the sub-surface and configured to surround the target substrate
on the main surface;

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